# A Low Dynamic Power and Low Leakage Power 90-nm CMOS Square-Root Circuit

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**Abstract** - To drastically reduce the dynamic power ( $P_{AT}$ ) and the leakage power ( $P_{ST}$ ), while to keep speed of a CMOS square-root (SR) circuit, a new algorithm, new architectures and a new leakage reduction circuit were developed. Using these techniques, a 90-nm CMOS LSI was fabricated. The  $P_{AT}$  and  $P_{ST}$  of the new SR circuit were reduced to about 1/4 and 1/33 those of a conventional SR circuit. Measured results agreed well with simulated results.

# **1. INTRODUCTION**

Low-power circuit techniques are needed for use in battery-driven portable systems. To reduce both the dynamic power  $(P_{\rm AT} = GCf_{\rm c}V_{\rm DD}^2)$  and the leakage power  $(P_{\rm ST} = GI_{\rm L}V_{\rm DD})$ of the CMOS circuits, we have to reduce the total number of logic gates (G), the supply voltage ( $V_{DD}$ ), and/or the leakage current  $(I_1)$  of an individual logic gate while maintaining a required clock frequency  $(f_c)$ . Improving both algorithms and architectures can reduce G. Shortening a critical path, that is, decreasing a number of logic gates  $(G_c)$  of the critical path can lower  $V_{DD}$ . Lowering  $V_{DD}$  is also effective for lowering  $I_{\rm L}$ . Furthermore, to drastically decrease  $I_{\rm L}$ , we developed a special leakage current reduction circuit. To examine the effects of the developed low power techniques on both  $P_{\rm AT}$  and  $P_{\rm ST}$ , we have applied those techniques to a square-root circuit for such uses as in computer graphic application.

## 2. TECHNIQUE FOR LOWERING SUPPLY VOLTAGE

Let  $Q = (a_1q_2 - q_m)$  be the square root of  $A = (a_1a_2 - a_{2m-1}a_{2m})$ . The *m*th-bit SR  $(q_m)$  is obtained as a carry signal when a *m*th reminder  $(.R_m)$  is calculated [1].  $R_m$  is obtained by

 $R_m = R_{m-1}a_{2m-1}a_{2m} - .00 - 0q_1q_2 - q_{m-2}q_{m-1}01$ (1) when  $q_{m-1}$  is 1. It is calculated as

 $R_m = R_{m-1}a_{2m-1}a_{2m} + .00 - 0q_1q_2 - q_{m-2}q_{m-1}11$  (2) when  $q_{m-1}$  is 0. The above two equations for *m* of 4 are carried out by the square-root (SR) circuit shown in Fig. 1 [1]. This 2*m*-bit conventional SR circuit (C-SR) for *m* of 4 can be constructed with a 4-stage ripple carry adder that consists of 20 full adders (CASs) with a subtraction function. Bold solid lines indicate the critical path. The C-SR including buffer inverters has *G* of 189 gates and *G*<sub>c</sub> of 60 gates in the critical path.

Replacing CASs by CAS1s and CAS2s (Fig.2) can drastically reduce  $G_c$ . G and  $G_c$  of the SR circuit for m of 4 would be reduced to 179 and 40, respectively. To further reduce G and  $G_c$ , we have modified Eq. 1 as

 $R_m = R_{m-1}a_{2m-1}a_{2m}+.11-.1q_{1,B}q_{2,B}-q_{m-2,B}q_{m-1,B}11$ , (3) where  $q_{1,B}$ ,  $q_{2,B}$ , and so on are the inverses of  $q_1$ ,  $q_2$ , and so on. Furthermore, 1 and  $q_{m-1,B}$  in Eq. 3 are replaced by  $q_{m-1}$ 



Fig. 1. A conventional square-root circuit (C-SR) for *m* of 4.



and 0, respectively. Similarly, 0 and  $q_{m-1}$  in Eq. 2 are replaced by  $q_{m-1}$  and 0, respectively. Thus, both Eqs. 2 and 3 can be expressed by the same equation as

$$R_m = .R_{m-1}a_{2m-1}a_{2m} + .q_{m-1}q_{m-1} - q_m$$

 $(q_1 \oplus q_{m-1})(q_2 \oplus q_{m-1})$ -- $(q_{m-2} \oplus q_{m-1})011$ . (4) *G* and *G*<sub>c</sub> of the SR circuit (not shown) using Eq. 4 for *m* of

4 were greatly reduced to 128 and 32, respectively.

The calculation processes of Eq. 4 are mostly carried out by additions, so complicated full adders (CAS-1 and CAS-2) with subtraction functions can mostly be replaced by either smaller full adders (FA, FA-1, FA-2) or simple half adders (HA-1, HA-2). Thus, we were able to significantly simplify the SR circuit (Fig. 2). *G* and  $G_c$  of the new SR circuit (N-SR) were greatly reduced to 95 and 30, respectively. Thus,



G and  $G_c$  of N-SR are about 50.0% of those of C-SR, respectively.

At  $V_{DD}$  of 1.0 V, the simulated maximum operating clock frequency ( $f_c$ ) of N-SR was 946 MHz, which was 1.66 times faster than that (= 570 MHz) of C-SR. This great  $f_c$ improvement was due to the considerable reduction of  $G_{\rm c}$ . The simulated  $P_{AT}$ s of C-SR and N-SR for *m* of 4 at  $f_c$  of 570 MHz are plotted as solid lines in Fig. 3. Between 0.5 V and 1.5 V,  $P_{AT}$  of N-SR is less than 50% of that of C-SR.  $P_{\rm AT}$  of N-SR at 0.77 V and 570 MHz is 131  $\mu$ W, which is 27.1% of that (484 µW at 1 V and 570 MHz) of C-SR. The simulated  $P_{ST}$ s of C-SR and N-SR for *m* of 4 are plotted as solid lines in Fig. 4. P<sub>ST</sub> of N-SR at 0.77 V is 276 nW, which is less than 1/4 of that (1,147 nW) of C-SR. Table 1 summarizes the characteristics of C-SR and N-SR.

## **3. LEAKAGE CURRENT REDUCTION CIRCUIT**

To further reduce  $P_{\rm ST}$ , we developed a leakage current reduction circuit called a "self-controllable-voltage-level (SVL)" circuit (Fig. 5). N-SR incorporating the SVL circuits is called N-SR-S. The upper SVL circuit (U-SVL) and the lower SVL circuit (L-SVL) can supply a maximum  $V_{\rm D}$  (=  $V_{\rm DD}$ ) and a minimum  $V_{\rm S}$  (=  $V_{\rm SS}$  = 0 V), respectively to the active N-SR on request (i.e., CLB = 0, CL = 1). The U-SVL and L-SVL can also supply decreased  $V_{\rm D}$  (<  $V_{\rm DD}$ ) and increased  $V_{\rm S}$  (> 0 V), respectively to the stand-by N-SR when CL is 0 and CLB is 1.

The SVL circuits can simultaneously reduce the drainto-source voltage  $(V_{ds})$  and increase the substrate bias  $(V_{sub})$ of cut-off MOSFETs. Thus, it decreases the sub-threshold currents of the cut-off MOSFETs [2]. The SVL circuit can also reduce the gate-to-drain electric fields of the cut-off MOSFETs and gate-to-source electric fields of the turn-on MOSFETs; it can reduce not only gate induced drain leakage (GIDL) currents in the cut-off MOSFETs [3], but also gate tunnel currents in the turn-on MOSFETs. Consequently,  $P_{\rm ST}$  of the SR circuit is considerably reduced.

At 1.0 V the maximum  $f_c$  of N-SR-S was 918 MHz, which was 3% slower than that (= 946 MHz) of N-SR. The simulated  $P_{AT}$  of N-SR-S for *m* of 4 at 570 MHz is plotted in Fig. 3. At 0.78 V  $P_{\rm AT}$  was reduced to 132  $\mu$ W that is 27.3% of that of C-SR. The simulated  $P_{\rm ST}$  of N-SR-S is plotted in Fig. 4. P<sub>ST</sub> of N-SR-S at 0.78 V is 34 nW, a reduction to 3% of C-SR and 12% of N-SR. The SVL

SR circuits	C-SR	N-SR (N-SR/C-SR)	N-SR-S (N-SR-S/C-SR)
No. of logic gates $G$	189	95 (50.3%)	97 (51.3%)
No. of logic gates of critical path G <sub>c</sub>	60 (100%)	30 (50.0%)	30 (50.0%)
Supply voltage V <sub>DD</sub> [V] *	1	0.77	0.78
Dynamic power $P_{AT}$ [µW] $f_{c}$ of 570 MHz **	484 (100%)	131 (27.1%)	132 (27.3%)
Leakage power P <sub>ST</sub> [nW]	1,147 (100%)	276 (24%)	$\frac{34}{(3\%V)}$

Table 1. Characteristics of C-SR, N-SR and N-SR-S.

\* Minimum  $V_{DD}$  that confirms the 570-MHz operation.

\*\*  $P_{\text{AT}}$  measured at  $f_{\text{c}}$  of 570 MHz.



circuit is very effective in reducing  $P_{\rm ST}$ , while the speed overhead is negligible.

#### 4. LSI FABRICATION AND EXPERIMENTAL RESULTS

C-SR, N-SR and N-SR-S were fabricated for m of 4 as shown in Fig. 6. The 90-nm, 6-layer Cu CMOS fabrication process was used. The threshold voltage  $(V_{th})$  of n-MOSFETs was 0.22 V and that of p-MOSFETs was -0.24 V. The measured  $P_{AT}$ s and  $P_{ST}$ s for the three circuits are plotted in Figs. 3 and 4, respectively. Measured results agree well with SPICE simulated results.

#### 5. SUMMARY

We have developed an SR algorithm, small circuit architectures, and a leakage current reduction circuit to reduce  $P_{AT}$  and  $P_{ST}$ , while maintaining operating speed. Our developed techniques hardly affected the operating speed, while reducing  $P_{\rm AT}$  to about 1/4 and  $P_{\rm ST}$  to 3% those of the conventional circuit. These power reduction techniques will therefore play a major role in future development of sub-100-nm CMOS circuits.

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